

IN THE CLAIMS

No claims have been amended.

1. (Previously Twice Amended) A process for recycling a vapor-phase chemical comprising:

introducing vapor-phase chemicals taken from the group consisting of NH_3 , N_2O , SiF_4 , SiH_4 , TiCl_4 , N_2 , Ar , HCl , and SiCl_4 and including pure H_2 gas into a reactor with sufficient supplied energy to cause a first reaction in said reactor;

exhausting gases from said reactor resulting from said first reaction;

separating a non-purified hydrogen gas from said exhausted gases;

venting said exhausted gases free of said non-purified hydrogen;

purifying said non-purified hydrogen gas to generate a purified H_2 gas; and thereafter introducing said purified H_2 gas into said reactor along with additional vapor-phase chemicals including pure H_2 gas into said reactor with sufficient supplied energy to cause a second reaction in said reactor.

2. (Previously Amended) A process for recycling a vapor-phase chemical comprising:

introducing vapor-phase chemicals including a first gas into a reactor with sufficient supplied energy to cause a first reaction in said reactor;

exhausting gases from said reactor resulting from said reaction;

separating a second gas from said exhausted gases;

purifying said second gas to generate a third gas; and thereafter introducing said third gas into said reactor along with said vapor-phase chemicals including said first gas into said reactor with sufficient supplied energy to cause a second reaction in said reactor, said first and second reactions including depositing a thin film layer on a substrate positioned in said reactor.

3. (Previously Twice Amended) The process of Claim 2, wherein said first gas comprises pure H_2 .

4. (Previously Twice Amended) The process of Claim 2, wherein said second gas comprises non-purified H₂.

5. (Previously Twice Amended) The process of Claim 2, wherein said third gas comprises between about 80% to 90% of the quantity of said pure H₂ introduced in said reactor.

6. (Previously Amended) The process of Claim 2, wherein the sufficient supplied energy comprises an RF low frequency power energy level of between about 0.318 watt/cm² to about 3.18 watts/cm².

7. (Previously Amended) The process of Claim 2, wherein said reactor comprises a tapered outer shell surrounding a tapered susceptor.

8. - 15. (Canceled)

16. (Previously Amended) The process of Claim 2, wherein said third gas comprises purified H₂.

17. - 22. (Canceled)

23. (Previously Amended) The process of Claim 2, wherein said vapor-phase chemicals comprise gases selected from the group consisting of NH₃, N₂O, SiF₄, SiH₄, TiCl₄, N₂, Ar, HCl, and SiCl₄.

24. (Previously Added) A process for recycling a by-product of a chemical reaction comprising:

introducing vapor-phase chemicals including first use hydrogen into a reactor with sufficient supplied energy to cause a first reaction for depositing a thin film layer on a substrate positioned in said reactor;

moving said second use hydrogen through a filter to convert said second use hydrogen to processing quality hydrogen; and thereafter

introducing said processing quality hydrogen into said reactor with said vapor-phase chemicals to be used in a second reaction for depositing a thin film layer on a substrate positioned in said reactor.

25. (Previously Added) The process of Claim 24, wherein said processing quality hydrogen comprises between about 80% to 90% of the quantity of said first use hydrogen introduced in said reactor.

26. (Previously Added) The process of Claim 24, wherein the sufficient supplied energy comprises an RF low frequency power energy level of between about 0.318 watt/cm^2 to about 3.18 watts/cm^2 .

27. (Previously Added) The process of Claim 24, wherein said reactor comprises a tapered outer shell surrounding a tapered susceptor.

28. (Previously Added) The process of Claim 24, wherein said vapor-phase chemicals comprise gases selected from the group consisting of NH_3 , N_2O , SiF_4 , SiH_4 , TiCl_4 , N_2 , Ar, HCl, and SiCl_4 .